IN THE SPECIFICATION

Please replace the paragraph beginning at page 1, line 2, with the following rewritten paragraph:

The present invention relates to multimetal oxide materials of the stoichiometry I $Mo_1V_aM^1_bM^2_cM^3_dO_n$ (I),

where

M¹ is at least one of the elements from the group consisting of Te and Sb;

M² is at least one of the elements from the group consisting of Nb, Ti, W, Ta and Ce;

M³ is at least one of the elements from the group consisting of Pb, Ni, CO Co, Bi, Pd, Ag, Pt, Cu, Au, Ga, Zn, Sn, In, Re, Ir, Sm, Sc, Y, Pr, Nd and Tb;

a is from 0.01 to 1,

b is from > 0 to 1;

c is from > 0 to 1;

d is from > 0 to 0.5 and

n is a number which is determined by the valency and frequency of the elements other than oxygen in (I),

whose X-ray diffraction pattern has reflections h, i and k whose peaks are at the diffraction angles $2(\odot)$ $22.2 \pm 0.5^{\circ}$ 2θ $22.2 \pm 0.5^{\circ}$ (h), $27.3 \pm 0.5^{\circ}$ $27.3 \pm 0.5^{\circ}$ (i) and $28.2 \pm 0.5^{\circ}$ $28.2 \pm 0.5^{\circ}$ (k),

- the reflection h being the one with the strongest intensity within the X-ray diffraction pattern and having an FWHH of not more than 0.5°,
- the intensity P_i of the reflection i and the intensity P_k of the reflection k fulfilling the relationship $0.65 \le R \le 0.85$, where R is the intensity ratio defined by the formula

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$$R = P_i/(P_i + P_k)$$

and

the FWHH of the reflection i and of the reflection k being in each case 1°, wherein the at least one multimetal oxide material (I) is one whose X-ray diffraction

Please replace the paragraph beginning at page 2, true line 28, with the following rewritten paragraph:

pattern has no reflection with the peak i position $2(\odot) = 50.0 + 0.3^{\circ} = 20 = 50.0 \pm 0.3^{\circ}$.

In the publications cited, this is attributable to the fact that, as a result of their preparation, these multimetal oxide materials are substantially present in crystalline form having a specific crystal structure, wherein their X-ray diffraction pattern has reflections with a strong intensity at the 20 peak positions $22.1 \pm 0.3^{\circ}$, $28.2 \pm 0.3^{\circ}$, $36.2 \pm 0.3^{\circ}$, $45.2 \pm 0.3^{\circ}$, $45.2 \pm 0.3^{\circ}$ and $45.2 \pm 0.3^{\circ}$, $45.2 \pm 0.3^{\circ}$, $45.2 \pm 0.3^{\circ}$ and $45.2 \pm 0.3^{\circ}$.

Please replace the paragraph beginning at page 3, line 1, with the following rewritten paragraph:

A second specific crystal structure in which the relevant multimetal oxide materials can occur is referred to as a rule as the i phase. Typical of its X-ray diffraction content, according to the abovementioned publications, is, inter alia, that it has reflections of the strongest intensity at the 2Θ peak positions $22.2 \pm 0.4^{\circ}$, $27.3 \pm 0.4^{\circ}$ and $28.2 \pm 0.4^{\circ}$, in contrast to the k phase in which, however, there is no reflection at the 2Θ peak position $50.0 \pm 0.3^{\circ}$ $50.0 \pm 0.3^{\circ}$.

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Please replace the paragraph beginning at page 5, true line 6, with the following rewritten paragraph:

In addition to the reflections h, i and k, the X-ray diffraction pattern of novel multimetal oxide materials (I) contains, as a rule, further reflections whose peaks are at the following diffraction angles $(2 \oplus 2 \ominus)$:

$$9.0 \pm 0.4^{\circ}$$
 9.0 \pm 0.40° (1),
6.7 \pm 0.4° (o) and
 $7.9 \pm 0.4^{\circ}$ 7.9 \pm 0.4° (p).

Please replace the paragraph beginning at page 5, true line 13, with the following rewritten paragraph:

It is furthermore advantageous if the X-ray diffraction pattern additionally contains a reflection whose peak is at the diffraction angle (2 Θ) of 45.2 + 0.4° (q).

Please replace the paragraph beginning at page 5, true line 16, with the following rewritten paragraph:

Frequently, the X-ray diffraction pattern of multimetal oxide materials (I) also contains the reflections $29.2 \pm 0.4^{\circ}$ (m) and $35.4 \pm 0.4^{\circ}$ (n) (peak positions).

Please replace the paragraph beginning at page 16, true line 33, with the following rewritten paragraph:

As stated above, what is important according to the invention is that the multimetal oxide materials (I) to be used according to the invention have an X-ray diffraction pattern (in this document, always based on Cu-K_{α} radiation) which has reflections h, i and k whose peaks are at the diffraction angles (20) $22.2 \pm 0.4^{\circ}$ (h), $27.3 \pm 0.4^{\circ}$ (i) and $28.2 \pm 0.4^{\circ}$ (28.2 $\pm 0.4^{\circ}$ (k),

- reflection h being the one with the strongest intensity within the x-ray diffraction pattern and having an FWHH of not more than 0.5°,
- intensity P_i of the reflection i and the intensity P_k of the reflection k fulfilling the relationship $0.65 \le R \pm 0.85$, where R is the intensity ratio defined by the formula

$$R = P_i/(P_i + P_k)$$

and

the FWHH of the reflection i and of the reflection k is in each case $\leq 1^{\circ}$.

Please replace the paragraph beginning at page 17, true line 11, with the following rewritten paragraph:

At the same time, the X-ray diffraction pattern should have no reflections with the peak position $2\theta = 50.0 + 0.3^{\circ}$ $2\theta = 50.0 \pm 0.3^{\circ}$.